

In the Claims

Please replace the claims with the following clean version of the entire set of pending claims. Cancel all previous versions of any pending claim. A marked-up version showing amendments to any claims being changed is provided in one or more accompanying pages separate from this amendment. Any claim not accompanied by a marked-up version has not been changed relative to the immediate prior version, except that marked-up versions are not being supplied for any added claim or canceled claim.

CLAIMS

1. (Amended) An etchant gas composition, comprising:
a carrier gas;
 C_4F_6 ;
 CH_2F_2 ; and
a gas selected from the group consisting of CHF_3 , CF_4 , and mixtures thereof.

Cancel claims 2 and 3.

4. The etchant gas composition according to Claim 1, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.
5. (Amended) The etchant gas composition according to Claim 1, wherein the carrier gas comprises argon.
6. (Amended) An etchant gas composition, consisting essentially of:
a carrier gas;
 C_4F_6 ;
 CH_2F_2 ; and
 CHF_3 .

Cancel claims 7 and 8.

9. The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

10. (Amended) The etchant gas composition according to Claim 6, wherein the carrier gas comprises argon.

11. (Amended) An etchant gas composition, consisting essentially of:

a carrier gas;

C_4F_6 ;

CH_2F_2 ; and

CF_4 .

Cancel claims 12 and 13.

14. The etchant gas composition according to Claim 11, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

15. (Amended) The etchant gas composition according to Claim 11, wherein the carrier gas comprises argon.

16. (Amended) An etchant gas composition, consisting essentially of:
a carrier gas;
 C_4F_6 ;
 CH_2F_2 ;
 CHF_3 ; and
 CF_4 .

Cancel claims 17 and 18.

19. The etchant gas composition according to Claim 16, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

20. (Amended) The etchant gas composition according to Claim 16, wherein the carrier gas comprises argon.

New Claims

Add new claim 65-74 as follows:

65. (Added) The etchant gas composition according to Claim 1 comprising O_2 .

66. (Added) The etchant gas composition according to Claim 1 comprising CO .

67. (Added) The etchant gas composition according to Claim 1 wherein the carrier gas comprises helium.

68. (Added) The etchant gas composition according to Claim 6 wherein the carrier gas comprises helium.

69. (Added) The etchant gas composition according to Claim 11 wherein the carrier gas comprises helium.

70. (Added) The etchant gas composition according to Claim 16 wherein the carrier gas comprises helium.

71. (Added) The etchant gas composition according to Claim 1 wherein the carrier gas comprises xenon.

72. (Added) The etchant gas composition according to Claim 6 wherein the carrier gas comprises xenon.

73. (Added) The etchant gas composition according to Claim 11 wherein the carrier gas comprises xenon.

74. (Added) The etchant gas composition according to Claim 16 wherein the carrier gas comprises xenon.